

WEST Search History

DATE: Monday, February 12, 2007

<u>Hide?</u>	<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>
<i>DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ</i>			
<input type="checkbox"/>	L8	L7 and l5	22
<input type="checkbox"/>	L7	134/2,3,19,26,28;216/96,99,108;438/906.ccls.	9637
<i>DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<input type="checkbox"/>	L6	L3 and ((clean\$3 or wash\$3 or etch\$3 or oxid\$5) same ozon\$5) and (hydrofluoric or (hydrogen fluoride) or HF)	2
<i>DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ</i>			
<input type="checkbox"/>	L5	L4 and ((clean\$3 or wash\$3 or etch\$3 or oxid\$5) same ozon\$5) and (hydrofluoric or (hydrogen fluoride) or HF)	500
<input type="checkbox"/>	L4	(wafer or substrate or workpiece or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sib.2")	8650
<i>DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<input type="checkbox"/>	L3	(wafer or substrate or workpiece or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sib.2")	4214
<i>DB=USPT; PLUR=YES; OP=ADJ</i>			
<input type="checkbox"/>	L2	6323140.pn.	1
<i>DB=PGPB; PLUR=YES; OP=ADJ</i>			
<input type="checkbox"/>	L1	20010053585	1

END OF SEARCH HISTORY

Searches for User *mkornnakov* (Count = 5180)

Queries 5131 through 5180.

S #	Updt	Database	Query
<u>S5180</u>	<u>U</u>	PGPB,USPT,USOC	(134/2,3,19,26,28;216/96,99,108;438/906.ccls.) and ((wafer or substrate or workpiece or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sib.2") and ((clean\$3 or wash\$3 or etch\$3 or oxid\$5) same ozon\$5) and (hydrofluoric or (hydrogen fluoride) or HF))
<u>S5179</u>	<u>U</u>	PGPB,USPT,USOC	134/2,3,19,26,28;216/96,99,108;438/906.ccls.
<u>S5178</u>	<u>U</u>	EPAB,JPAB,DWPI,TDBD	((wafer or substrate or workpiece or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sib.2")) and ((clean\$3 or wash\$3 or etch\$3 or oxid\$5) same ozon\$5) and (hydrofluoric or (hydrogen fluoride) or HF)
<u>S5177</u>	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or workpiece or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sib.2")) and ((clean\$3 or wash\$3 or etch\$3 or oxid\$5) same ozon\$5) and (hydrofluoric or (hydrogen fluoride) or HF)
<u>S5176</u>	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or workpiece or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sib.2"))
<u>S5175</u>	<u>U</u>	EPAB,JPAB,DWPI,TDBD	((wafer or substrate or workpiece or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sib.2"))
<u>S5174</u>	<u>U</u>	USPT	6323140.pn.
<u>S5173</u>	<u>U</u>	PGPB	20010053585
<u>S5172</u>	<u>U</u>	PGPB,USPT,USOC	(((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3")) and (hydrofluoric or HF or (hydrogen fluoride)))

S5171	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3")) and (134/2,3,26;438/906.cccls.)	2 (((
S5170	<u>U</u>	PGPB,USPT,USOC	(134/2,3,26;438/906.cccls.) and (((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3") and (hydrofluoric or HF or (hydrogen fluoride)))	2 (((
S5169	<u>U</u>	PGPB,USPT,USOC	134/2,3,26;438/906.cccls.	2 (((
S5168	<u>U</u>	PGPB,USPT,USOC	134/2,3,26;438/906.cccls.	2 (((
S5167	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3")) and (hydrofluoric or HF or (hydrogen fluoride))	2 (((
S5166	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3")	2 (((
S5165	<u>U</u>	EPAB,JPAB,DWPI,TDBD	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3") same (hydrofluoric or HF or (hydrogen fluoride))	2 (((
S5164	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3") same (hydrofluoric or HF or (hydrogen fluoride))	2 (((
S5163	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same ((clean\$3 or wash\$3 or rins\$3 or oxid\$7) with (ozon\$4 or "O.sub.3") with (hydrofluoric or HF or (hydrogen fluoride)))	2 ((((
S5162	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same ((clean\$3 or wash\$3 or rins\$3 or oxid\$7) with (ozon\$4 or "O.sub.3"))	2 ((((
S5161	<u>U</u>	EPAB,JPAB,DWPI,TDBD	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same ((clean\$3 or wash\$3 or rins\$3 or oxid\$7) with (ozon\$4 or "O.sub.3"))	2 ((((
S5160	<u>U</u>	EPAB,JPAB,DWPI,TDBD	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")) same ((clean\$3 or wash\$3 or rins\$3 or oxid\$7) with (ozon\$4 or "O.sub.3"))	2 ((((
S5159	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) adj7 (hydrogen or	2 ((((

		"H.sub.2")) same ((clean\$3 or wash\$3 or rins\$3 (or oxid\$7)) with (ozon\$4 or "O.sub.3"))	2
S5158	U	((wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")) same ((clean\$3 or wash\$3 or rins\$3 (or oxidiz\$5)) with (ozon\$4 or "O.sub.3"))	2
S5157	U	((wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")) with (clean\$3 or wash\$3 or rins\$3) with (ozon\$4 or "O.sub.3"))	2
S5156	U	((wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")) with (clean\$3 or wash\$3 or rins\$3) with (ozon\$4 or "O.sub.3"))	2
S5155	U	((wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")) with (clean\$3 or wash\$3 or rins\$3))	2
S5154	U	((wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")) with (clean\$3 or wash\$3 or rins\$3))	2
S5153	U	((wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")))	2
S5152	U	((wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")))	2
S5151	U	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2") same oxidiz\$5) same (hydrofluoric or HF)	2
S5150	U	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2") same oxidiz\$5) same (hydrofluoric or HF)	2
S5149	U	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2")) same oxidiz\$5	2
S5148	U	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2")) same (ozon\$4 with water)	2
S5147	U	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2")) same (ozon\$4 adj5 water)	2
S5146	U	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2")) same (ozon\$4 adj3 water)	2
S5145	U	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2"))	2
S5144	U	((wafer or substrate) same ((anneal\$3 or heat\$3)	2

S5143 U EPAB,JPAB,DWPI with (hydrogen or "h.sub.2") same (hydrofluoric or HF) same (ozon\$4 adj3 water) (wafer or substrate) same ((anneal\$3 or heat\$3) with (hydrogen or "h.sub.2") same (hydrofluoric or HF) same (ozon\$4 adj3 water))

S5142 U PGPB,USPT,USOC,EPAB,JPAB,DWPI((toshiba ceramics).as. or izumome-koji\$.in. or sakurai-naoaki\$.in. or hayamizu-naoya\$.in. or yamabe-jyunsei\$.in. or ino-takao\$.in. or nagahama-hiromi\$.in. or kurita-hisatsugu\$.in.) and ((wafer or substrate) same ((anneal\$3 or heat\$3) with (hydrogen or "h.sub.2") same (hydrofluoric or HF) same (ozon\$4 adj3 water)))

S5141 U PGPB,USPT,USOC,EPAB,JPAB,DWPI((toshiba ceramics).as.) or (izumome-koji\$.in.) or (sakurai-naoaki\$.in.) or (hayamizu-naoya\$.in.) or (yamabe-jyunsei\$.in.) or (ino-takao\$.in.) or (nagahama-hiromi\$.in.) or (kurita-hisatsugu\$.in.)

S5140 U PGPB,USPT,USOC,EPAB,JPAB,DWPI(toshiba ceramics).as.

S5139 U PGPB,USPT,USOC,EPAB,JPAB,DWPI izumome-koji\$.in.

S5138 U PGPB,USPT,USOC,EPAB,JPAB,DWPI(izumome-koji)\$..in.

S5137 U PGPB,USPT,USOC,EPAB,JPAB,DWPI(shibata-izumome)\$..in.

S5136 U PGPB,USPT,USOC,EPAB,JPAB,DWPI((shibata-shi)-izumome)\$..in.

S5135 U PGPB,USPT,USOC,EPAB,JPAB,DWPI sakurai-naoaki\$.in.

S5134 U PGPB,USPT,USOC,EPAB,JPAB,DWPI hayamizu-naoya\$.in.

S5133 U PGPB,USPT,USOC,EPAB,JPAB,DWPI yamabe-jyunsei\$.in.

S5132 U PGPB,USPT,USOC,EPAB,JPAB,DWPI ino-takao\$.in.

S5131 U PGPB,USPT,USOC,EPAB,JPAB,DWPI nagahama-hiromi\$.in.